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(71) Applicant: LAM RESEARCH CORPORATION

[US/US]; 4650 Cushing Pkwy., Fremont, California 94538 (US).

(72) Inventors; and

(71) Applicants: KUMAR, Harish [IN/IN]; 4650 Cushing Pkwy., Fremont, California 94538 (US). GUO, Tongtong

[CN/US]; 4650 Cushing Pkwy., Fremont, California 94538 (US). BATZER, Rachel E. [US/US]; 4650 Cushing Pkwy., Fremont, California 94538 (US). GONG, Bo [CN/US]; 4650 Cushing Pkwy., Fremont, California 94538 (US). JUAREZ, Francisco J. [US/US]; 4650 Cushing Pkwy., Fremont, California 94538 (US). CHANG, Ching-Yun [CN/US]; 4650 Cushing Pkwy., Fremont, California 94538 (US).

(74) Agent: SCHOLZ, Christian D. et al.; WEAVER AUSTIN VILLENEUVE & SAMPSON LLP, P.O. Box 70250, Oakland, California 94612-0250 (US).

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(54) Title: APPARATUSES FOR CLEANING A MULTI-STATION SEMICONDUCTOR PROCESSING CHAMBER

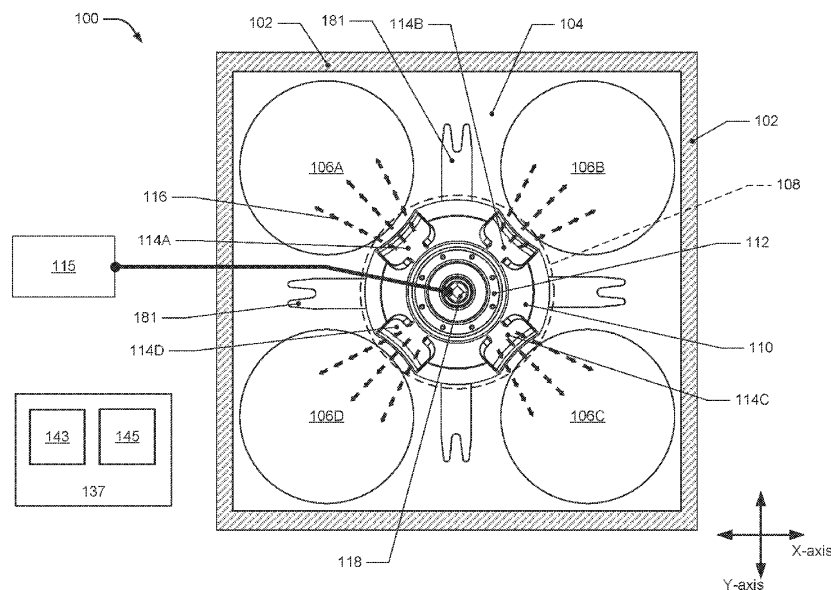


Figure 1A

(57) Abstract: Disclosed are various systems that allow for plasma delivery from a central location in a multi-station processing chamber to be redirected to different processing stations within the chamber. Such systems may include a deflector plate that is mounted to a wafer indexer such that the deflector plate is centered on the wafer indexer. In other implementations, such systems may include a deflector plate that is mounted in a fixed relationship with a ceiling of the processing chamber.

[Continued on next page]

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